



10/Response
J. Steptoe
3/30/01

RECEIVED
THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Smith, et al.

Docket No: TI-25250

Serial No: 09/199,829

Examiner: K. Eaton

Filed: 11/25/98

Art Unit: 2823

For: HYDROGEN PLASMA PHOTORESIST STRIP AND POLYMERIC RESIDUE
CLEANUP PROCESS FOR OXYGEN-SENSITIVE MATERIALS

RESPONSE PURSUANT TO 37 CFR 1.116

Assistant Commissioner for Patents
Washington, DC 20231

MAILING CERTIFICATE UNDER 37 C.F.R. § 1.8(a)

I hereby certify that the above correspondence is being deposited with the U.S. Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Assistant Commissioner for Patents, Washington, DC 20231 on 3-22-01.


Ann Trent

Dear Sir:

Responsive to the Office Action mailed January 3, 2001, in connection with the above identified application, Applicants respectfully submit the following remarks. Please charge any necessary fees to the deposit account of Texas Instruments, Inc., Account No. 20-0668.